WEST Search History

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DATE: Friday, March 30, 2007

Hide?	Set Name	Query	Hit Count
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L19	((wafer or substrate or semiconductor or object) with (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)) same (((back plate) or (lower side) or plate or shield$3) with (hydrophobic or polymer or resin or teflon) with (surface tension))	2
		DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L18	((wafer or substrate or semiconductor or object) with (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)) same (((back plate) or (lower side) or plate or shield$3) with (hydrophobic or polymer or resin or teflon) with (surface tension))	1
☐	L17	L16 same (liquid or solution or solvent or wet$4 or fluid)	49
☐	L16	(wafer or substrate or semiconductor or object) with (clean$3 or treat$3 or rins$3 or wash$3 or etch$3) with ((back plate) or (lower side) or plate or shield$3) adj5 (hydrophobic or polymer or resin or teflon)	139
☐	L15	L14 same (liquid or solution or solvent or wet$4 or fluid)	82
☐	L14	((wafer or substrate or semiconductor or object) with (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)) same (((back plate) or (lower side) or plate or shield$3) adj5 (hydrophobic or polymer or resin or teflon))	214
☐	L13	L12 same (liquid or solution or solvent or wet$4 or fluid)	383
☐	L12	((wafer or substrate or semiconductor or object) with (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)) same (((back plate) or (lower side) or plate or shield$3) with (hydrophobic or polymer or resin or teflon))	876
☐	L11	L10 same (liquid or solution or solvent or wet$4 or fluid)	582
☐	L10	(wafer or substrate or semiconductor or object) same (clean$3 or treat$3 or rins$3 or wash$3 or etch$3) same (((back plate) or (lower side) or plate or shield$3) with (hydrophobic or polymer or resin or teflon))	1289
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L9	L8 and l5	17
☐	L8	(wafer or substrate or semiconductor or object) same (clean$3 or treat$3 or rins$3 or wash$3 or etch$3) same (((back plate) or (lower side) or plate or shield$3) with (hydrophobic or polymer or resin or teflon))	2515
☐	L7	(wafer or substrate or semiconductor or object) same (clean$3 or treat$3 or rins$3 or wash$3 or etch$3) same (((back plate) or (lower side) or plate or shield$3 or back) with (hydrophobic or polymer or resin or teflon))	3055
		DB=USPT,EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	
☐	L6	L5 and l2	10
☐	L5	134/137,139,149,154,182,153,201,902;156/345.23,345.3.ccls.	4285
		DB=EPAB,JPAB,DWPI; PLUR=YES; OP=ADJ	

☐ L4 l3 same (liquid or solution or solvent or wet$4 or fluid) 521

☐ L3 (wafer or substrate or semiconductor or object) same (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)same (((back plate) or (lower side) or plate shield$3 or back) with (hydrophobic or polymer or resin or silicon or teflon)) 1823

DB=USPT; PLUR=YES; OP=ADJ

☐ L2 L1 same (liquid or solution or solvent or wet$4 or fluid) 1165

☐ L1 (wafer or substrate or semiconductor) same (clean$3 or treat$3 or rins$3 or wash$3 or etch$3)same (((back plate) or (lower side) or plate shield$3 or back) with (hydrophobic or polymer or resin or silicon or teflon)) 5693

END OF SEARCH HISTORY